



## IIU-IDB ADVANCED ELECTRONICS LABORATORIES PROJEC **Process Characterization Auxiliary Facilities-02**

## Fume Hood Wet Bench for Cleaning, Etching and **Sample Preparation**

Fume Hood and Wet Bench in the lab are used to clean debris and to etch away unwanted or no longer needed films from wafers or device surfaces. They are also used to prepare a wafer's surface for the next step in the overall process. Front End of Line refers to the manufacturing processes that manufacture the transistor portion of an integrated circuit. The hood in the lab is capable of making Resist Strip, Nitride etch or strip, Residue clean, post etch, or post ash clean, Oxide etch and STI (shallow trench isolation) clean.

## MEMS Grade Spin Coating, Baking and Stirring

The high resist film thickness homogeneity as well as the short coating times makes spin-coating the most-applied coating technique at least in microelectronics.

